

1 1. (cancelled)

1 2. (cancelled)

1 3. (previously presented) A maskless lithography system comprising an array of apodized
2 diffractive elements, each of which focuses an energy beam into an array of images in order to
3 create a permanent pattern on an adjacent substrate at a focal area and is apodized to reduce at
4 least one of the main or side lobes in an intensity distribution at a focal area.

1 4. (original) The maskless lithography system as claimed in claim 3, wherein apodized
2 diffractive elements are Fresnel zone plates.

1 5. (original) The maskless lithography system as claimed in claim 3, wherein apodized
2 diffractive elements are Fresnel phase plates.

1 6. (original) The maskless lithography system as claimed in claim 3, wherein apodized
2 diffractive elements are blazed Fresnel zone plates.

1 7. (original) The maskless lithography system as claimed in claim 3, wherein said apodized
2 diffractive elements are formed of photon sieves.

1 8. (original) The maskless lithography system as claimed in claim 7, wherein said photon
2 sieves are amplitude photon sieves.

1 9. (original) The maskless lithography system as claimed in claim 7, wherein said photon
2 sieves are phase photon sieves.

1 10. (original) The maskless lithography system as claimed in claim 7, wherein said photonic
2 sieves are alternating phase photonic sieves.

1 11. (original) A maskless lithography system comprising an array of diffractive elements,
2 each of which focuses an energy beam into an array of images in order to create a permanent
3 pattern on an adjacent substrate and has a focusing efficiency of at least 50%.

1 12. (original) The maskless lithography system as claimed in claim 11, wherein said
2 diffractive elements are 100% transmissive.

1 13. (original) The maskless lithography system as claimed in claim 12, wherein said
2 diffractive elements are alternating phase photon sieves.

1 14. (previously presented) A maskless lithography system comprising an array of Bessel
2 zone plates, each of which converts an energy beam into an array of Bessel beams in order to
3 create a permanent pattern on an adjacent substrate.

1 15. (new) The maskless lithography system as claimed in claim 11, wherein said diffractive
2 elements are blazed Fresnel zone plates.

1 16. (new) The maskless lithography system as claimed in claim 11, wherein said diffractive
2 elements are apodized Fresnel zone plates.

- 1 17. (new) A maskless lithography system comprising an array of apodized phase photon
- 2 sieves, each of which focuses an energy beam into an array of images in order to create a
- 3 permanent pattern on an adjacent substrate at a focal area and is apodized to reduce at least one
- 4 of the main or side lobes in an intensity distribution at a focal area.